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(Use several sheets if necessary)APPLICANT
Steven Gerard Mayorga, et al.

FILING DATE

GROUP

(37 CFR 1.98(b))

U.S. PATENT DOCUMENTS

EXAM- INER INITIAL	DOCUMENT NUMBER								DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPRO- PRIATE
	5	0	2	8	5	6	6		7/2/91	Andre Lagendijk	437	238	7/27/90
	5	5	4	8	0	0	6		8/20/96	Satao Hirabayashi, et al	524	82	11/17/94
	5	3	8	0	8	1	2		1/10/95	Michael A. Lutz, et al	528	15	1/10/94
	3	3	4	4	1	1	1		9/26/67	Alan J. Chalk	260	46.5	9/26/66
	3	8	8	2	0	8	3		5/6/75	Abe Berger, et al	260	46.5	11/21/73
	3	9	9	8	8	6	5		12/21/76	George Siciliano, et al	260	448.2	3/12/75
	2	8	3	7	5	5	0		6/3/58	Maurice Prober	260	448.2	5/18/55
	6	3	6	8	3	5	9		4/9/02	R. J. Perry, et al	8	142	12/17/99

FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER								DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
												YES	NO
7	1	4	5	1	7	9		8/25/99	JP	C07F	7/21	X	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	"User's Guide For: Glass Deposition With Teos," Dr. Arthur K. Hochberg, Schumacher, 1992.
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	"Modeling of Low-Pressure Deposition of SiO ₂ by Decomposition...", Huppertz, et al, Schumacher, 1979.
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	"Ion and Chemical Radical Effects on the Step Coverage...", C.-P. Chang, et al, J. Appl. Phys. 67, 1990.
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	"User's Guide For: Undoped Glass, PSG, and BPSG Using...", Schumacher, 1991.
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	English language translation JP 07-145179.
	JP 07 145179 A: Patent Abstracts of Japan, vol. 1995, No. 09, 10/31/95.
	XP-002233220: Derwent Publications Ltd., London, GB; AN 1980-10616C.
	XP-002233221: Derwent Publications Ltd., London, GB; AN 1997-72075Y.
	European Search Report EP 02 02 8017

EXAMINER

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EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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